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-	APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
	10/615,881	07/10/2003	Jae-Hyun Yeo	9862-000015/US/CPA	8462
	30593	7590 03/08/2005		EXAMINER	
	HARNESS,	DICKEY & PIERCE,	NGUYEN, TUAN H		
	P.O. BOX 8910 RESTON, VA 20195			ART UNIT	PAPER NUMBER
				2813	
				DATE MAILED: 03/08/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)				
		10/615,881	YEO ET AL.				
	Office Action Summary	Examiner	Art Unit				
		Tuan H. Nguyen	2813				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply							
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).							
Status							
1)⊠	1) Responsive to communication(s) filed on <u>01 December 2004</u> .						
•	·	s action is non-final.					
3)	· ·						
Disposit	ion of Claims						
5)□ 6)⊠ 7)□	4) ☐ Claim(s) 1-29 is/are pending in the application. 4a) Of the above claim(s) 1-18 is/are withdrawn from consideration. 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 19-29 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or election requirement.						
Applicat	ion Papers						
9)	9)☐ The specification is objected to by the Examiner.						
10)	10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.						
	Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.							
Priority (under 35 U.S.C. § 119						
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 							
Attachmen	at(s)						
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 4) Interview Summary (PTO-413) Paper No(s)/Mail Date 5) Notice of Informal Patent Application (PTO-152) 6) Other:							

DETAILED ACTION

Election/Restrictions

Applicant's election with traverse of Group II, claims 19-29 in the reply filed on 12/1/04 is acknowledged. The traversal is on the ground(s) that "Examiner would not be unduly burdened if forced to examine the claims of both Group I and Group II in the same application". This is not found persuasive because a method for forming a dielectric layer is not a method for forming a capacitor. They are patentably distinct species, and no claim is generic.

Should applicant traverse on the ground that the species are not patentably distinct, applicant should submit evidence or identify such evidence now of record showing the species to be obvious variants or clearly admit on the record that this is the case. In either instance, if the examiner finds one of the inventions unpatentable over the prior art, the evidence or admission may be used in a rejection under 35 U.S.C. 103(a) of the other invention.

The requirement is still deemed proper and is therefore made FINAL.

Claim Rejections - 35 USC § 112

The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claim 29 is rejected under 35 U.S.C. 112, second paragraph, as being incomplete for omitting essential elements, such omission amounting to a gap between the elements. See MPEP § 2172.01. The omitted elements are: Process steps for

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forming a dielectric layer. Note that an independent claim can not depend on another independent claim.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371(c) of this title before the invention thereof by the applicant for patent.

The changes made to 35 U.S.C. 102(e) by the American Inventors Protection Act of 1999 (AIPA) and the Intellectual Property and High Technology Technical Amendments Act of 2002 do not apply when the reference is a U.S. patent resulting directly or indirectly from an international application filed before November 29, 2000. Therefore, the prior art date of the reference is determined under 35 U.S.C. 102(e) prior to the amendment by the AIPA (pre-AIPA 35 U.S.C. 102(e)).

Claims 19-27, 29 are rejected under 35 U.S.C. 102(e) as anticipated by or, in the alternative, under 35 U.S.C. 103(a) as obvious over either Lim et al. or Koh et al..

See Lim et al., figs. 1-7 and related text on pages 1-7 which discloses the claimed method for forming a dielectric film for a DRAM by ALD (see paragraphs [0024]-[0025]) including the supply metal alkoxide precursor into a reactor, purging, and

supply oxidant that contains no hydroxyl group including ozone followed by purging.

This cycle is repeated one or more times until the layer is formed to a desired thickness (see paragraphs [0056], [0067]).

With respect to claims 20, 21, see Lim et al., claim 22, 23.

With respect to claim 27, see paragraph [0078]-[0084] for a metal oxide film made of an oxidized mixture of a metal M_1 and another metal M_2 .

See also Koh et al., figs. 1-4 and related text on pages 3-9 which discloses the use of ALD method for forming a dielectric material layer for capacitor in DRAM (paragraph [0037]), including the use of metal alkoxide group and oxygen gas O₂.

With respect to claim 22, see Koh et al. paragraph [0059].

Both Lim et al. and Koh et al are silent about the first and second electrodes of the capacitor; however, it would have been obvious to one having ordinary skill in the art at the time the invention was made to have recognized that the dielectric formed in a memory device as disclosed by Lim et al. in paragraph [0025] or koh et al. paragraph [0037] would inherently include a capacitor having the disclosed dielectric sandwiched between first and second electrodes.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claim 28 is rejected under 35 U.S.C. 103(a) as being unpatentable over Lim et al..

Lim et al., figs. 1-7 and related text on pages 1-7 discloses substantially the claimed method for forming a dielectric film for a DRAM by ALD except the formation of aluminum dielectric layer over hafnium dielectric layer; however, Lim et al. in paragraph [0079]-[0081] teaches the process of alternately stacking and oxidizing different two metal oxides to form a metal oxide film.

It would have been obvious to one having ordinary skill in the art at the time the invention was made to have formed a stacked dielectric layer of aluminum oxide over hafnium oxide from the metals group as suggested by Lim et al. in paragraph [0067] for preventing leakage current, and Increasing in dielectric constant.

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Skarp et al., Callegari et al., Tois et al., and Ritala et al. are citred as of interest.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Tuan H. Nguyen whose telephone number is 571-272-1694. The examiner can normally be reached on 9AM-5:30PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead Jr. can be reached on 571-272-1702. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Tuan H. Nguyen / Primary Examiner Art Unit 2813